

Supporting information

Insight into a complexation mechanism between BiVO₄ photoanode and tartaric acid for efficient photoelectrochemical H₂ production

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Experimental section

Fabrication of ZnO photoanode

The ZnO photoanode was synthesized using a hydrothermal method.¹ First, 0.44 g of zinc nitrate hexahydrate and 0.22 g of hexamethylenetetramine was dissolved in 60 ml of water and transferred to a 100 ml autoclave. An FTO glass substrate with an Al foil-covered edge was inserted into the autoclave with its conducting surface facing downwards. The autoclave was maintained at 90 °C for 4 h and cooled down naturally. The resulting photoanode was rinsed with water and ethanol before being left to dry overnight. The final product was a ZnO photoanode.

Fabrication of TiO₂ photoanode

The TiO₂ photoanode was prepared using a hydrothermal method, as described in previous studies.² In brief, a white solution containing 30 ml of hydrochloric acid, 30 ml of water, and 1.0 ml of titanium n-butoxide was transferred into a autoclave along with an FTO glass (conducting surface down). The autoclave was then maintained at 150 °C for 5 h, followed by a natural cooling process. The resulting sample was rinsed with water and dried, and subsequently annealed at 550 °C for 4 h. Finally, the TiO₂ photoanode was obtained.

Fabrication of WO₃ photoanode

The WO₃ photoanode was synthesized via a hydrothermal and annealing process.³ Initially, 0.5 g of sodium tungstate dihydrate was dissolved in 60 ml of water and vigorously stirred. Next, 12 ml of 3.0 M hydrochloric acid and 0.4 g of ammonium oxalate were added to the solution and stirred vigorously again. The resulting solution was transferred to a 100 ml autoclave containing an upside-down FTO substrate. The autoclave was then heated to 120 °C for 12 h before being allowed to cool naturally. The obtained product was rinsed with water and dried at 60 °C for 5 h. The sample was then annealed at 500 °C for 1 h. Finally, the WO₃ photoanode was finally obtained after cooling the sample.

Characterizations

The structures and morphologies of the prepared photoanodes were characterized using X-ray diffraction (XRD, Bruker D8-Advance) and scanning electron microscopy (SEM, Hitachi S-4800). Ultraviolet-visible diffuse reflectance spectroscopy (UV-Vis DRS) measurements of the photoanodes were performed by a UV-vis spectrophotometer (Shimadzu 2550) equipped with an integrating sphere, with BaSO₄ serving as the reference material. The elements chemical states and chemical environment of the prepared photoanodes were determined by X-ray photoelectron spectroscopy (XPS, Thermo Fisher Scientific Escalab Xi+) using a monochromatic Al-K α source. The C1s peak at 284.8 eV was used to calibrated the peak positions of the measured elements.

Calculation details

The first-principles density functional theory (DFT) simulations were performed utilizing Vienna *ab initio* simulation package with the generalized gradient approximation (GGA) and Perdew-Burke-Ernzerhof (PBE) exchange-correlation function.⁴⁻⁶ To illustrate the interaction between valence electrons and ionic cores, the projected augmented wave (PAW) potentials with a plane wave basis set were adopted, while the kinetic cut-off energy was set to 450 eV.^{7, 8} To determine the partial occupancies of Kohn-Sham orbitals, the Gaussian smearing method with a width of 0.05 eV were used. The electronic energy was reckoned as self-consistent under the condition that the energy change is within 10⁻⁵ eV and the geometry optimization of atomic structure was reckoned as convergent under the condition that the energy change is within 0.05 eV Å⁻¹. The vacuum spacing is 20 Å for the surface system in the direction that perpendicular to plane. The Brillouin zone integration were performed by a 4×5×1 k-points sampling under the Monkhorst-Pack scheme. And the adsorption energy (E_{ad}) were calculated by the follow equation:

$$E_{ads} = E_{ad-sub} - E_{ad} - E_{sub}$$

Where E_{ad-sub} is the total energy of the optimized system, E_{ad} is the energy of adsorbate and the E_{sub} is the energy of substrate.

Supplementary data

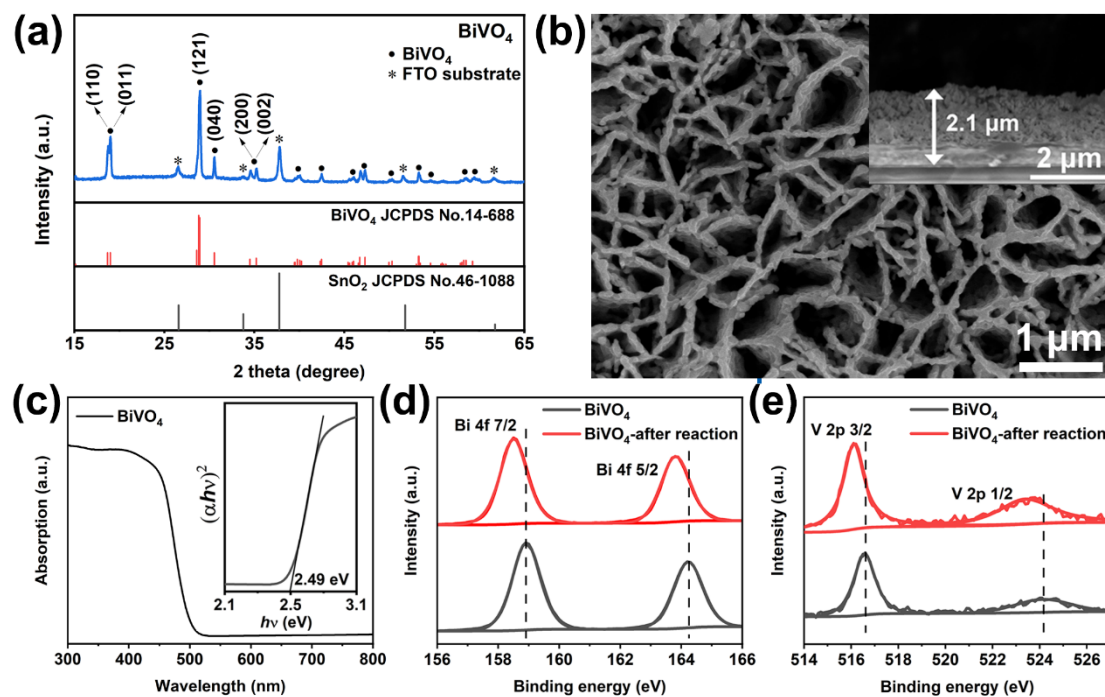


Fig. S1 (a) XRD pattern, (b) top and the inserted cross-sectional view SEM images, (c) UV-Vis DRS spectrum and the inserted Tauc-plot of the BiVO₄ photoanode. (d) Bi 4f and (e) V 2p XPS peaks of the BiVO₄ photoanode before and after the PEC test in KPi + 0.5 M C₄H₆O₆ solution.

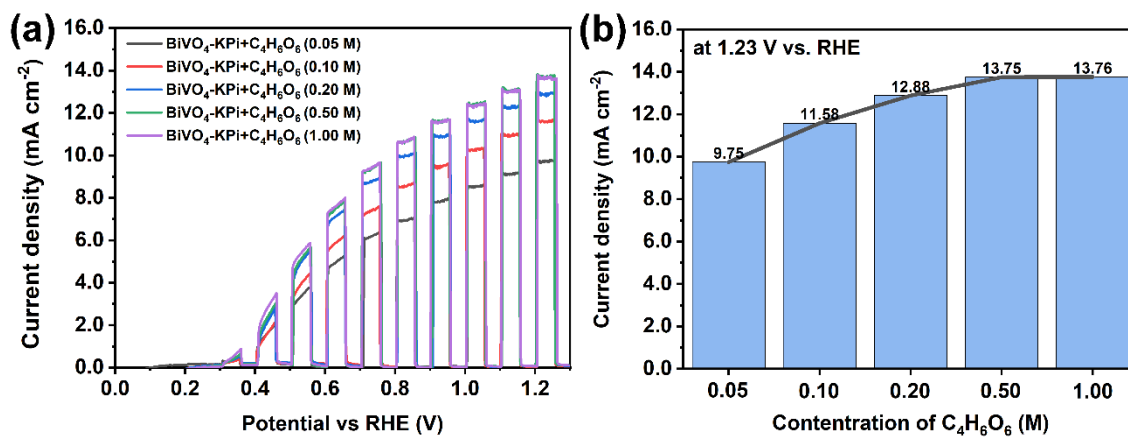


Fig. S2 (a) Current density-potential (J-p) curves of the BiVO₄ photoanode under AM 1.5 G irradiation or in the dark in KPi + C₄H₆O₆ solution with different concentrations of C₄H₆O₆. (b) Current density of the BiVO₄ photoanode at 1.23 V versus RHE in KPi + 0.5 M C₄H₆O₆ solution with different concentrations of C₄H₆O₆.

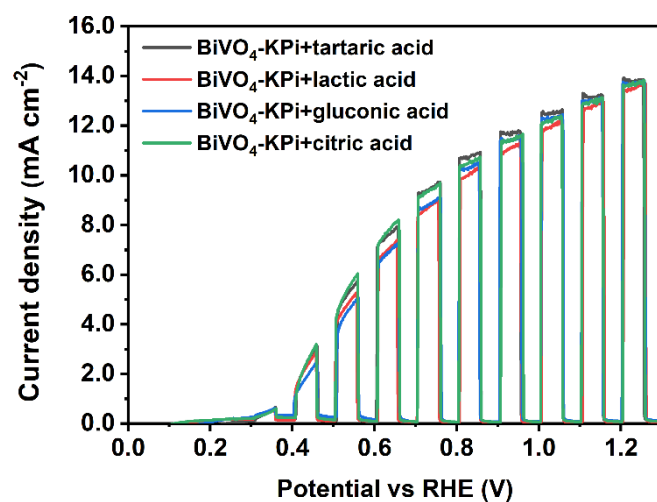


Fig. S3 J-p curves of the BiVO₄ photoanode under AM 1.5 G irradiation or in the dark in KPi + 0.5 M tartaric acid (C₄H₆O₆), KPi + 0.5 M lactic acid, KPi + 0.5 M gluconic acid, and KPi + 0.5 M citric acid solutions.

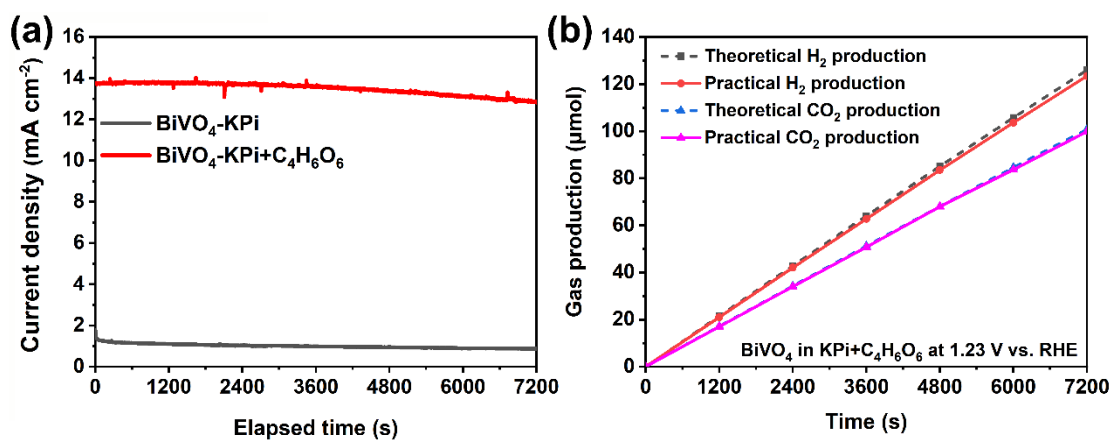


Fig. S4 (a) Current density-time (J-t) curves of the BiVO₄ photoanode measured at 1.23 V versus RHE in KPi and KPi + 0.5 M C₄H₆O₆ solutions. (b) Theoretical and practical H₂ and CO₂ production of the BiVO₄ photoanode measured at 1.23 V versus RHE in KPi + 0.5 M C₄H₆O₆ solution.

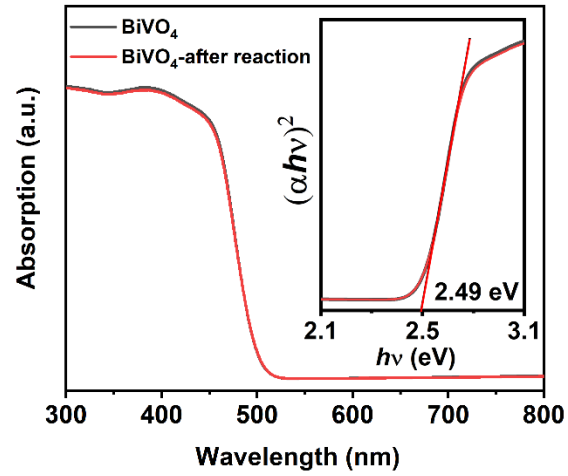


Fig. S5 UV-vis DRS spectrum and the inserted Tauc-plot of the BiVO₄ photoanode before and after the PEC test in KPi + 0.5 M C₄H₆O₆ solution.

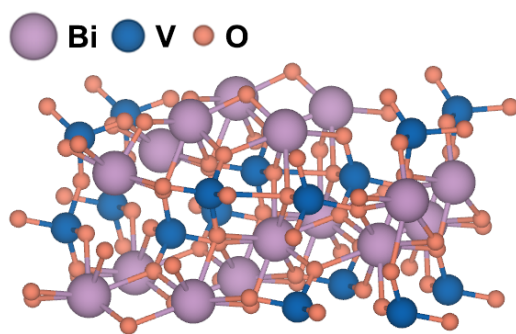


Fig. S6 Simulated structure of the BiVO₄ (121) surface after geometric optimization (the purple, blue and orange spheres represent Bi, V, and O atoms in turn).

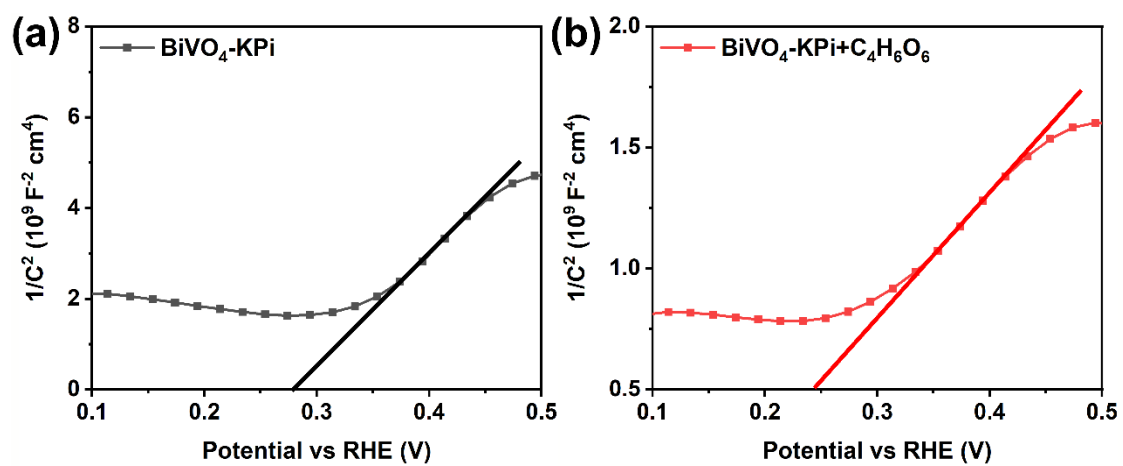


Fig. S7 Mott-Schottky plots of the BiVO₄ photoanode in (a) KPi and (b) KPi + 0.5 M C₄H₆O₆ solutions.

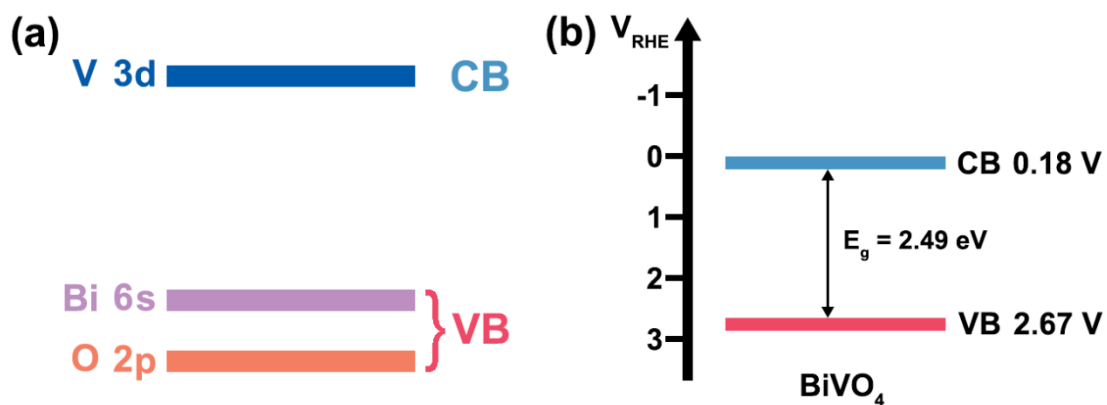


Fig. S8 Schematic diagram of (a) the band structure and (b) the band positions of BiVO₄.

In the case of an n-type semiconductor, it is generally accepted that the flat band potential obtained by Mott-Schottky measurement is assumed to be situated at approximately 0.1 eV below the CB.¹ The flat band potential of BiVO₄ photoanode obtained from Mott-Schottky measurement is 0.28 V vs. RHE. Therefore, the CB position of BiVO₄ is calculated to be 0.18 V vs. RHE. Moreover, the bandgap of BiVO₄ obtained by Tauc-plot is 2.49 eV. Finally, the VB position of BiVO₄ is determined to be 2.67 V vs. RHE.

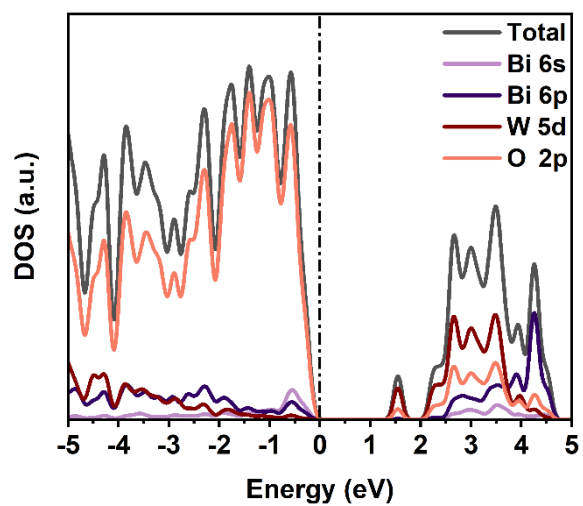


Fig. S9 (a) Total DOS (TDOS) and partial DOS (PDOS) of Bi_2WO_6 .

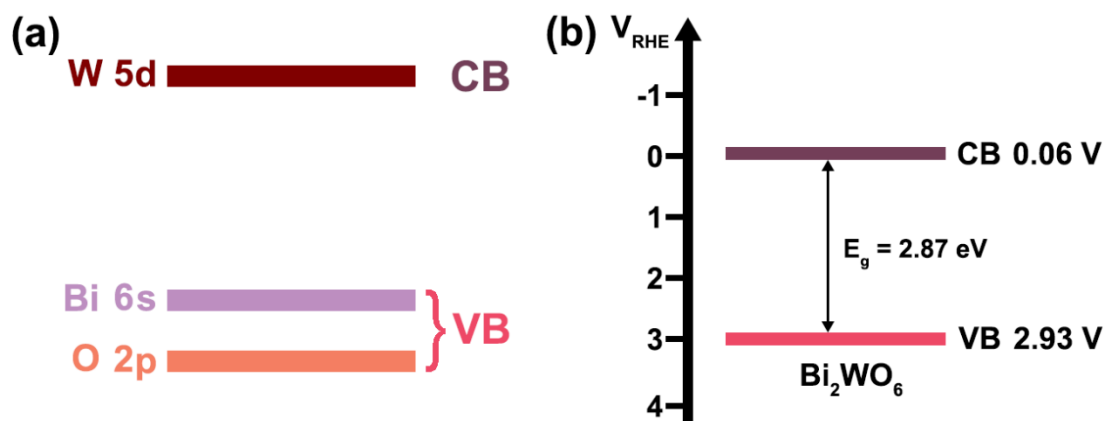


Fig. S10 Schematic diagram of (a) the band structure and (b) the band positions of Bi_2WO_6 .

The flat band potential of Bi_2WO_6 photoanode obtained from Mott-Schottky measurement is 0.16 V vs. RHE. Therefore, the CB position of Bi_2WO_6 is calculated to be 0.06 V vs. RHE. Moreover, the bandgap of Bi_2WO_6 obtained by Tauc-plot is 2.87 eV. Finally, the VB position of Bi_2WO_6 is determined to be 2.93 V vs. RHE.

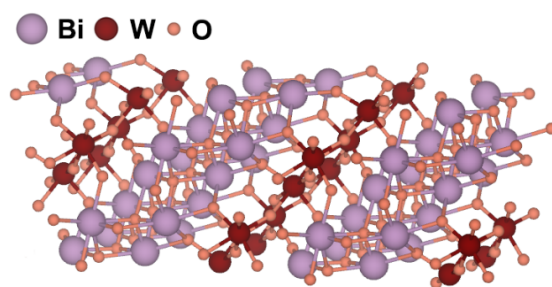


Fig. S11 Simulated structure of the Bi₂WO₆ (026) surface after geometric optimization (the purple, crimson, and orange spheres represent Bi, W, and O atoms in turn).

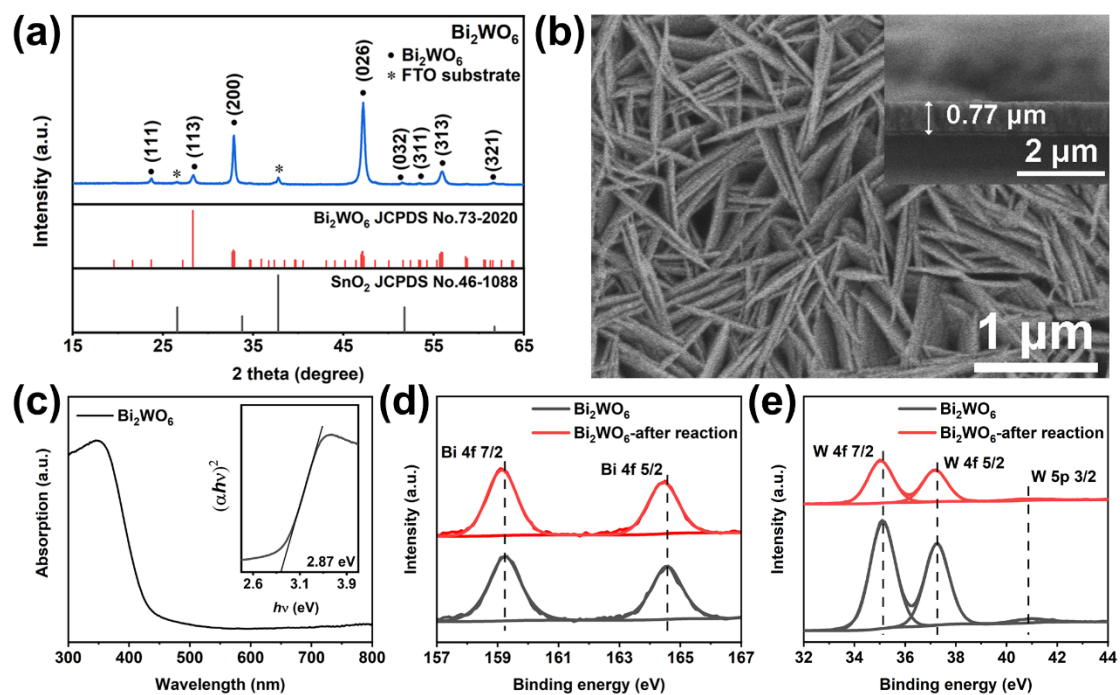


Fig. S12 (a) XRD pattern, (b) top and the inserted cross-sectional view SEM images, (c) UV-vis DRS spectrum and the inserted Tauc-plot of the Bi₂WO₆ photoanode. (d) Bi 4f and (e) W 4f and W 5p XPS peaks of the Bi₂WO₆ photoanode before and after the PEC test in KPi + 0.5 M C₄H₆O₆ solution.

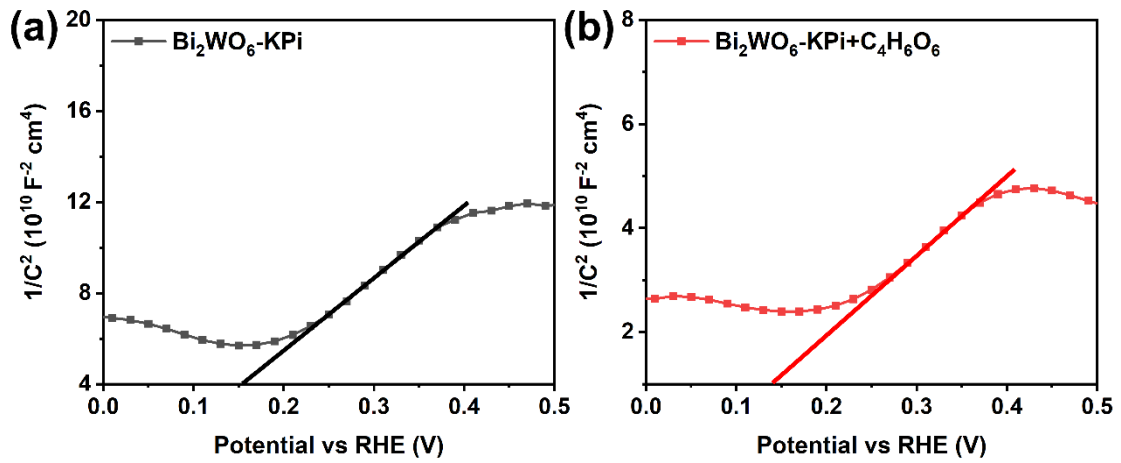


Fig. S13 Mott-Schottky plots of the Bi₂WO₆ photoanode in (a) KPi and (b) KPi + 0.5 M C₄H₆O₆ solutions.

The calculated donor densities (N_d) of Bi₂WO₆ photoanode in KPi and KPi + C₄H₆O₆ solutions are 8.27×10^{18} and $2.04 \times 10^{19} \text{ cm}^{-3}$, respectively.

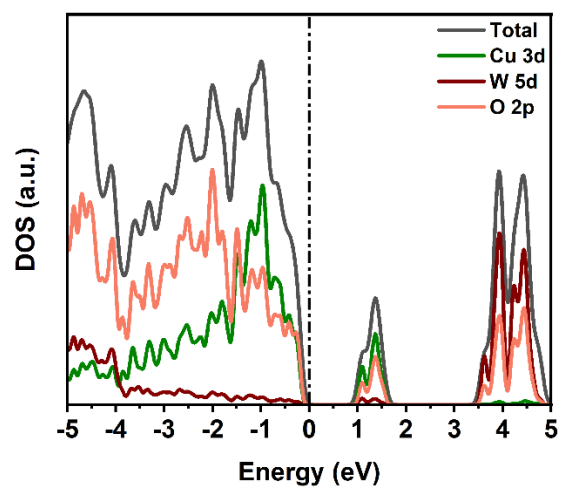


Fig. S14 TDOS and PDOS of CuWO₄.

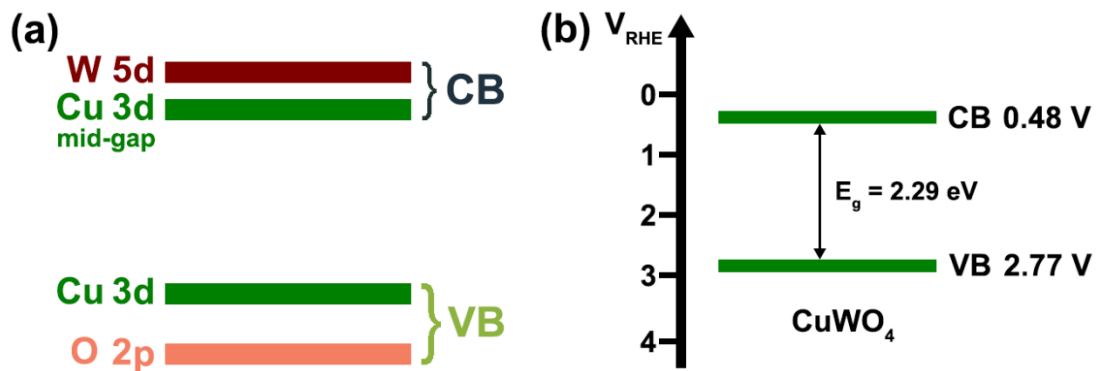


Fig. S15 Schematic diagram of (a) the band structure and (b) the band positions of CuWO₄.

The flat band potential of CuWO₄ photoanode obtained from Mott-Schottky measurement is 0.58 V vs. RHE. Therefore, the CB position of CuWO₄ is calculated to be 0.48 V vs. RHE. Moreover, the bandgap of CuWO₄ obtained by Tauc-plot is 2.29 eV. Finally, the VB position of CuWO₄ is determined to be 2.77 V vs. RHE.

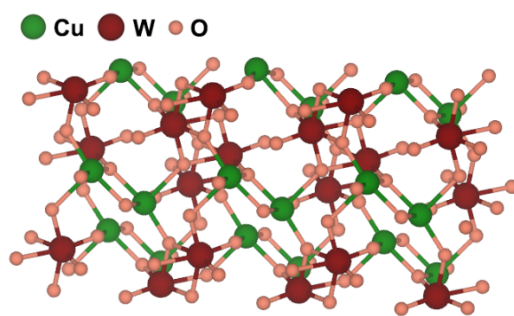


Fig. S16 Simulated structure of the CuWO₄ (110) surface after geometric optimization (the green, crimson and orange spheres represent Cu, W, and O atoms in turn).

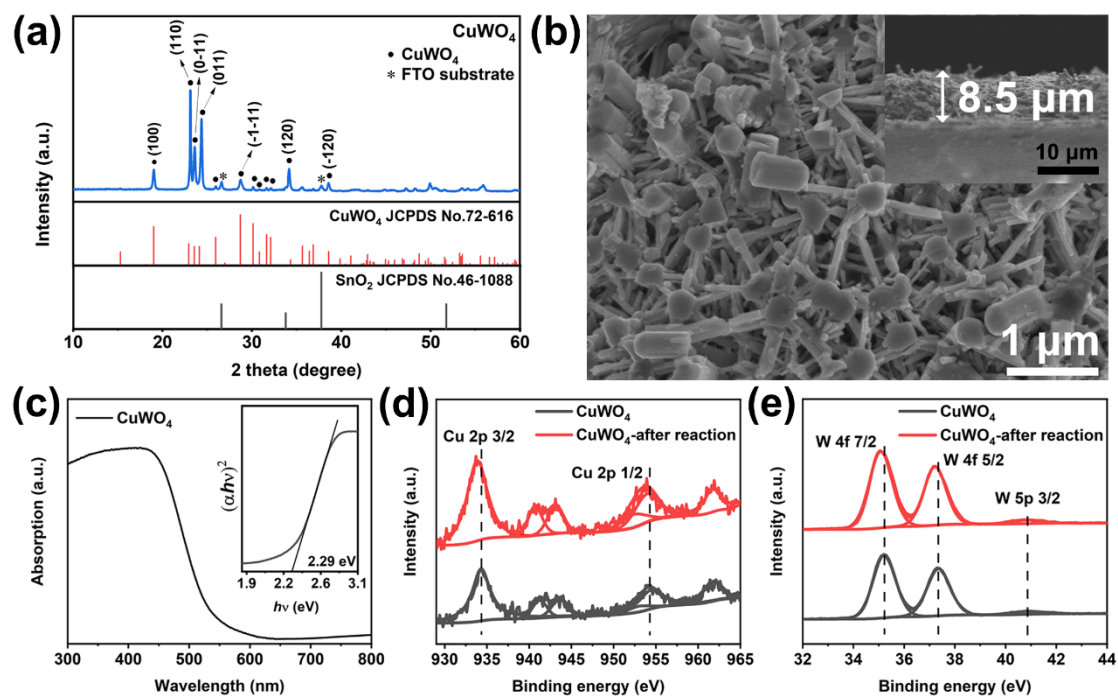


Fig. S17 (a) XRD pattern, (b) top and the inserted cross-sectional view SEM images, (c) UV-vis DRS spectrum and the inserted Tauc-plot of the CuWO_4 photoanode. (d) Cu 2p and (e) W 4f and W 5p XPS peaks of the CuWO_4 photoanode before and after the PEC test in $\text{KPi} + 0.5 \text{ M C}_4\text{H}_6\text{O}_6$ solution.

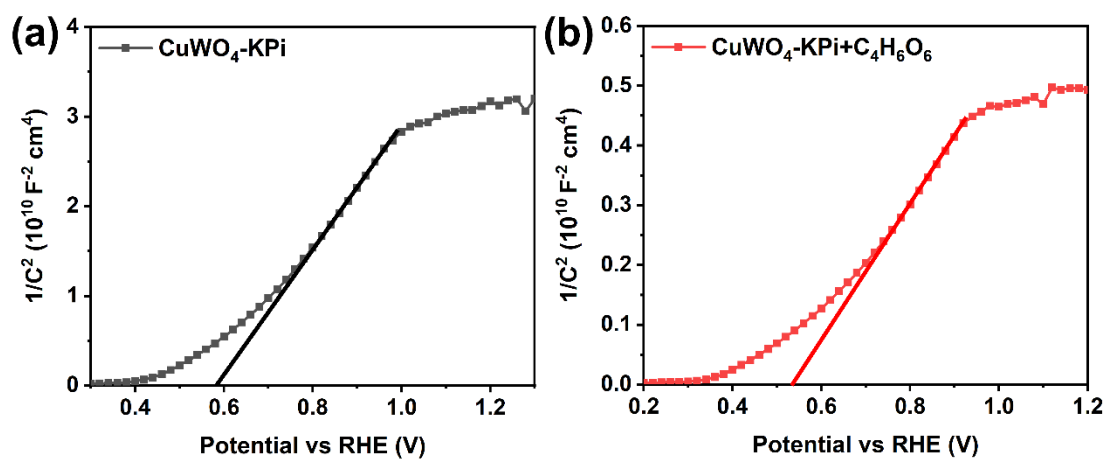


Fig. S18 Mott-Schottky plots of the CuWO₄ photoanode in (a) KPi and (b) KPi + 0.5 M C₄H₆O₆ solutions.

The calculated N_d for CuWO₄ photoanode in KPi and KPi + C₄H₆O₆ solutions are 2.30×10^{19} and $1.53 \times 10^{20} \text{ cm}^{-3}$, respectively.



Fig. S19 Schematic diagram of the band structure of ZnO, TiO₂, and WO₃.

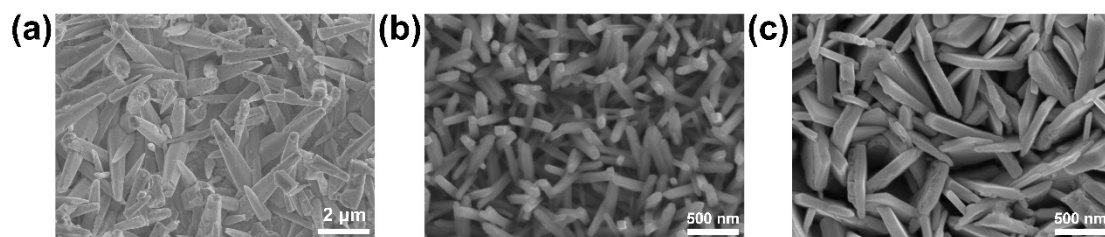


Fig. S20 SEM images of the (a) ZnO, (b) TiO₂, and (c) WO₃ photoanode.

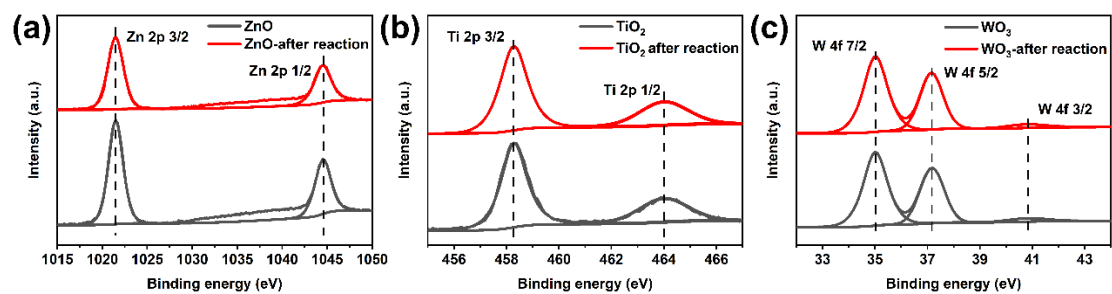


Fig. S21 (a) Zn 2p XPS peaks of the ZnO photoanode, (b) Ti 2p XPS peaks of the TiO₂ photoanode, and (c) W 5p XPS peaks of the WO₃ photoanode before and after the PEC test in KPi + 0.5 M C₄H₆O₆ solution.

References

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